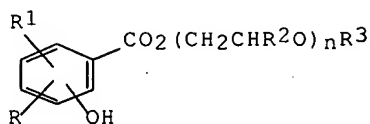


L31 ANSWER 53 OF 66 HCAPLUS COPYRIGHT 2007 ACS on STN
 ACCESSION NUMBER: 1980:207138 HCAPLUS Full-text
 DOCUMENT NUMBER: 92:207138
 TITLE: Photopolymerizable mixture
 INVENTOR(S): Faust, Raimund Josef; Lehmann, Peter
 PATENT ASSIGNEE(S): Hoechst A.-G., Fed. Rep. Ger.
 SOURCE: Ger. Offen., 35 pp.
 CODEN: GWXXBX
 DOCUMENT TYPE: **Patent**
 LANGUAGE: German
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
DE 2822191	A1	19791122	DE 1978-2822191	19780520 <--
EP 6125	A1	19800109	EP 1979-101411	19790509 <--
EP 6125	B1	19830511		
R: BE, CH, DE, FR, GB, IT, NL, SE				
CA 1128802	A1	19820803	CA 1979-327826	19790517 <--
JP 54153623	A	19791204	JP 1979-60573	19790518 <--
JP 62045968	B	19870930		
PRIORITY APPLN. INFO.:			DE 1978-2822191	19780520 <--
GI				



AB Photopolymerizable compns. for use as photoresists and in the fabrication of printing plates are composed of a binder that is soluble or swellable in aqueous alkaline solution, an addition polymerizable compound with ≥ 2 acrylic acid or methacrylic acid ester groups and a b.p. $>100^\circ$, a photoinitiator, and a plasticizer having the formula I (R = H, halogen, C1-4 alkyl; R1 = H, OH, C1-4 alkyl; R2 = H, Me; R3 = C1-20 alkyl or alkenyl and contains ≥ 4 C atoms when n = 0 or 1; n = 0-20). The compns. give developed images which adhere well to metal supports and are resistant to etching solns. Thus, a photopolymerizable composition containing hexyl methacrylate-methacrylic acid-styrene copolymer (60:30:10 wt parts; average mol wt 35,000) 6.5, a diurethane prepared by reaction of 2,2,4-trimethylhexamethylene diisocyanate 1 mol with hydroxymethyl acrylate 2 mol 2.8, a polyurethane prepared by reacting 2,2,4-trimethylhexamethylene diisocyanate 11 mol with triethylene glycol 10 mol and then with hydroxyethyl methacrylate 2 mol 2.8, 9-phenylacridine 0.2, 3-mercaptopropionic acid 2,4-dichloroanilide 0.1, a blue azo dye 0.035, the ester of diethylene glycol mono-2-ethylhexyl ether with 2,6-dihydroxybenzoic acid 2.8, MeCOEt 35, and EtOH 2 g was coated on a biaxial oriented and heat-fixed PET support at 28 g/m² (dry), laminated on a Cu-laminated phenolic plate, imagewise exposed, spray developed with 0.8% Na₂CO₃, washed, etched, and galvanized. The plate showed no undercutting or damage.

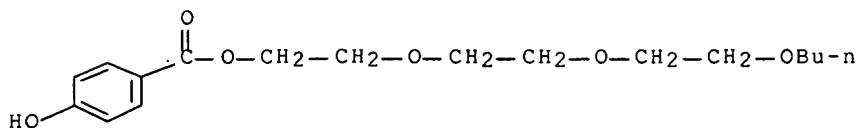
IT 64524-57-8 73639-18-6 73639-19-7
 73639-20-0 73639-21-1 73639-22-2
 73639-23-3 73639-25-5 73651-70-4

73651-72-6 73689-07-3

RL: MOA (Modifier or additive use); USES (Uses)

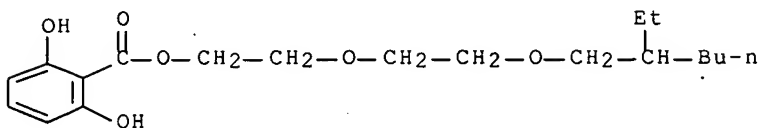
(plasticizer, for photopolymerizable compns. for photoresists and printing plates)

RN 64524-57-8 HCAPLUS

CN Benzoic acid, 4-hydroxy-, 2-[2-(2-butoxyethoxy)ethoxy]ethyl ester (9CI)
(CA INDEX NAME)

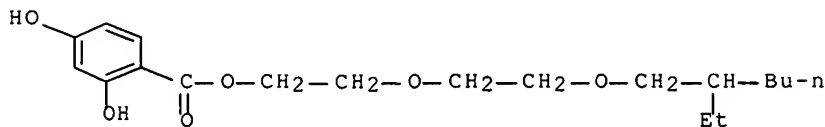
RN 73639-18-6 HCAPLUS

CN Benzoic acid, 2,6-dihydroxy-, 2-[2-[(2-ethylhexyl)oxy]ethoxy]ethyl ester (9CI) (CA INDEX NAME)



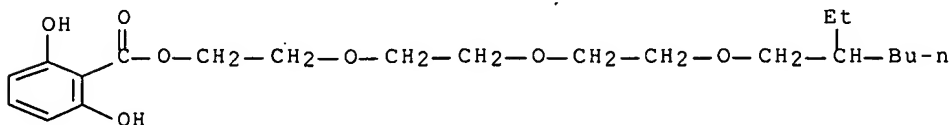
RN 73639-19-7 HCAPLUS

CN Benzoic acid, 2,4-dihydroxy-, 2-[2-[(2-ethylhexyl)oxy]ethoxy]ethyl ester (9CI) (CA INDEX NAME)



RN 73639-20-0 HCAPLUS

CN Benzoic acid, 2,6-dihydroxy-, 2-[2-[2-[(2-ethylhexyl)oxy]ethoxy]ethoxy]ethyl ester (9CI) (CA INDEX NAME)

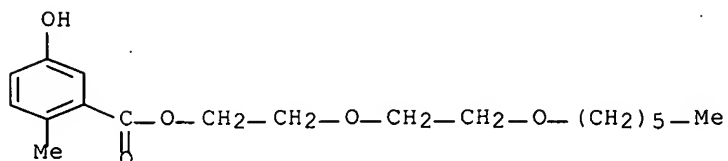


RN 73639-21-1 HCAPLUS

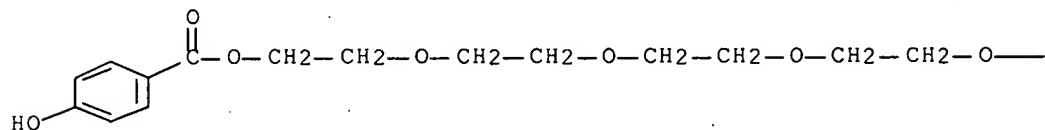
CN Benzoic acid, 2,6-dihydroxy-, 20-ethyl-3,6,9,12,15,18-hexaoxatetracos-1-yl ester (9CI) (CA INDEX NAME)

[illegible]
$$\text{---CH}_2\text{---O---CH}_2\text{---CH}_2\text{---O---CH}_2\text{---}\overset{\text{Et}}{\underset{|}{\text{CH}}}\text{---Bu-n}$$
COC(=O)c1ccc(O)cc1OCCOCCOCCOCCCCCCOCCOCCOCC(=O)c1ccccc1OCCCCC(C)COC(=O)c1ccc(O)cc1

RN 73651-70-4 HCAPLUS

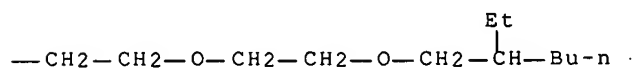
CN Benzoic acid, 5-hydroxy-2-methyl-, 2-[2-(hexyloxy)ethoxy]ethyl ester (9CI)
(CA INDEX NAME)

RN 73651-72-6 HCAPLUS

CN Benzoic acid, 4-hydroxy-, 20-ethyl-3,6,9,12,15,18-hexaoxatetracos-1-yl
ester (9CI) (CA INDEX NAME)

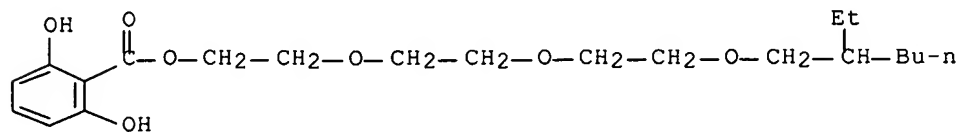
PAGE 1-A

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RN 73689-07-3 HCAPLUS

CN Benzoic acid, 2,6-dihydroxy-, 2-[2-[2-[(2-ethylhexyl)oxy]methylethoxy]methylethoxy]methylethyl ester (9CI) (CA INDEX NAME)



3 (D1-Me)